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10/796,704	03/09/2004	Toru Takayama	10873.1414US01	2943
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EXAMINER				
FORDE, DELMA ROSA				
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Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary

Application No.

10/796,704

Applicant(s)

TAKAYAMA, TORU

Examiner

Delma R. Fordé

Art Unit

2828

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 25 April 2008.
- 2a) ☒ This action is **FINAL**. 2b) ☐ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 16, 18-20, 22-26 and 29-39 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 16, 18-20, 22-26 and 29-39 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. _____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☐ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO/SB/808)
Paper No(s)/Mail Date _____
- 4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date _____
- 5) ☐ Notice of Informal Patent Application
- 6) ☐ Other: _____

DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 16, 18 – 20, 22 – 23, 30 – 35 and 39 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shimoyama Kenji (JP 2000-312052).

Regarding claim 16, Shimoyama shown in Figures 1 – 3, discloses a semiconductor laser device formed on a tilted substrate (see Fig. 1A Character 101) composed of a compound semiconductor, comprising an active layer (see Fig. 1A Character 106) and two cladding layers (see Fig. 1A and 1B Characters 102 and 111) interposing the active layer therebetween, wherein one of the cladding layers (see Fig. 1B, Character 111, and Paragraph [0048-0049]) forms a mesa-shaped (see Fig. 1B, Character 110, Paragraphs [0013, 0026-0027 and 0055-0056], the reference call “stripe-like opening”) the ridge includes a first region (see Fig. 3a, Character W_c) where a width of a bottom portion of the ridge is substantially constant, and a second region

(See Fig. 3a, Characters W_t) where the width of the bottom portion of the ridge is varied continuously, and the second region (see Fig. 3a, Characters W_t) is placed between the first region (see Fig. 3a, Character W_c) and an end face (see Fig. 3a, Character W_R) in an optical path, and end face in an optical path.

Shimoyama discloses the claimed invention except for width of the bottom portion of the ridge in the first region is in a range of $1.8\text{ }\mu\text{m}$ to $2.5\text{ }\mu\text{m}$, the width of the bottom portion of the ridge in the second region is in a range of $2.4\text{ }\mu\text{m}$ to $3\text{ }\mu\text{m}$, and the resonator length is in a range of $800\text{ }\mu\text{m}$ to $1500\text{ }\mu\text{m}$. It would have been obvious to one having ordinary skill in the art at the time the invention was made to different width of the bottom portion of the ridge in the first and second region and a resonator length, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233.

In addition, the selection of different width of the bottom portion of the ridge in the first and second region and a resonator length, it's obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. *In re Woodruff*, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also *In re Huang*, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996) (claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they

produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also *In re Boesch*, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and *In re Aller*, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed [width of the bottom portion of the ridge in the first region is in a range of 1.8 μm to 2.5 μm , the width of the bottom portion of the ridge in the second region is in a range of 2.4 μm to 3 μm , and the resonator length is in a range of 800 μm to 1500 μm] or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen [width of the bottom portion of the ridge in the first region is in a range of 1.8 μm to 2.5 μm , the width of the bottom portion of the ridge in the second region is in a range of 2.4 μm to 3 μm , and the resonator length is in a range of 800 μm to 1500 μm] or upon another variable recited in a claim, the Applicant must show that the chosen [width of the bottom portion of the ridge in the first region is in a range of 1.8 μm to 2.5 μm , the width of the bottom portion of the ridge in the second region is in a range of 2.4 μm to 3 μm , and the resonator length is in a range of 800 μm to 1500 μm] are critical. *In re Woodruff*, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Shimoyama discloses the claimed invention except for length of the first region is 10% to 50% with respect to a resonator length. It would have been obvious to one having ordinary skill in the art at the time the invention was made to a length of the first

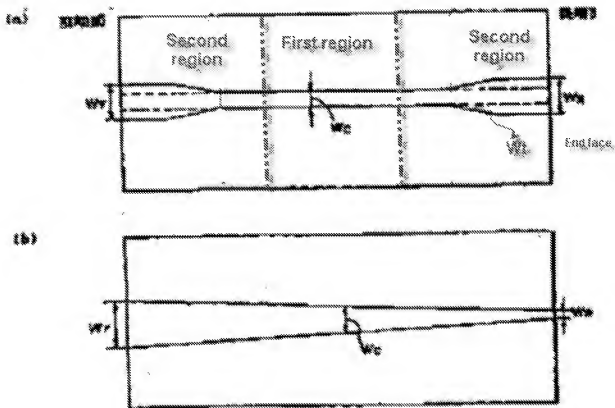
region with respect to the resonator length, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233.

In addition, the selection of a region with respect to a resonator length, it's obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. *In re Woodruff*, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also *In re Huang*, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996) (claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also *In re Boesch*, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and *In re Aller*, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed [a length of the first region being 10% to 50% with respect to a resonator length] or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen [a length of the first region being 10% to 50% with respect to a resonator length] or upon another variable recited in a claim, the Applicant must show that the chosen [a length of the first region being 10% to 50% with respect to a

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resonator length] are critical. *In re Woodruff*, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).



Regarding claims 18, 31, Shimoyama discloses the claimed invention except for the length of the first region is 10% to 20% with respect to the resonator length. It would have been obvious to one having ordinary skill in the art at the time the invention was made to length of the first region with respect to the resonator length, since it has been held that where the general conditions of a claim are disclosed in the prior art,

discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233.

In addition, the selection of length of the first region with respect to the resonator length, its obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. *In re Woodruff*, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also *In re Huang*, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996) (claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also *In re Boesch*, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and *In re Aller*, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed [the length of the first region is 10% to 20% with respect to the resonator length] or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen [the length of the first region is 10% to 20% with respect to the resonator length] or upon another variable recited in a claim, the Applicant must show that the chosen [the length of the first region is 10% to 20% with respect to the resonator length] are critical. *In re Woodruff*, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Regarding claims 19, 29, 32 and 39, Shimoyama discloses the claimed invention except for length of the first region is 100 μm or more, and the resonator length is in a range of 800 μm to 1200 μm . It would have been obvious to one having ordinary skill in the art at the time the invention was made to length of the first region and the resonator length, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233.

In addition, the selection of length of the first region and the resonator length, its obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. *In re Woodruff*, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also *In re Huang*, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996) (claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also *In re Boesch*, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and *In re Aller*, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed [length of the first region is 100 μm or more, and the resonator length is in a

range of 800 μm to 1200 μm] or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen [length of the first region is 100 μm or more, and the resonator length is in a range of 800 μm to 1200 μm] or upon another variable recited in a claim, the Applicant must show that the chosen [length of the first region is 100 μm or more, and the resonator length is in a range of 800 μm to 1200 μm] are critical. *In re Woodruff*, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Regarding claims 20 and 33, Shimoyama shown in Figures 1 – 3, discloses differential resistance R_s in current voltage characteristics is 6.5 Ω or less (Paragraph 60).

Regarding claims 22 and 34, Shimoyama shown in Figures 1 – 3, discloses the second region is placed between the first region and one end face in the optical path and between the first region and the other end face in the optical path (see Figure 3A).

Regarding claims 23 and 35, Shimoyama shown in Figures 1 – 3, discloses at a boundary between the first region and the second region, the width of the bottom portion of the ridge in the first region is substantially the same as that in the second region (see Figure 3A and 3B).

Regarding claim 30, Shimoyama shown in Figures 1 – 3, discloses a semiconductor laser device formed on a tilted substrate (see Fig. 1A Character 101) composed of a compound semiconductor, comprising an active layer (see Fig. 1A Character 106) and two cladding layers (see Fig. 1A and 1B Characters 102 and 111) interposing the active layer therebetween, wherein one of the cladding layers (see Fig. 1B, Character 111, and Paragraph [0048-0049]) forms a mesa-shaped (see Fig. 1B, Character 110, Paragraphs [0013, 0026-0027 and 0055-0056], the reference call “stripe-like opening”) the ridge includes a first region (see Fig. 3a, Character W_C) where a width of a bottom portion of the ridge is substantially constant, and a second region (See Fig. 3a, Characters W_t) where the width of the bottom portion of the ridge is varied continuously, and the second region (see Fig. 3a, Characters W_t) is placed between the first region (see Fig. 3a, Character W_C) and an end face (see Fig. 3a, Character W_R) in an optical path, and end face in an optical path.

Shimoyama discloses the claimed invention except for width of the bottom portion of the ridge in the first region is in a range of 1.8 μm to 2.5 μm , a difference between the width of the bottom portion of the ridge in the first region and a maximum width of the bottom portion of the ridge in the second region is in a range of 0.5 μm or less, and the resonator length is in a range of 800 μm to 1500 μm . It would have been obvious to one having ordinary skill in the art at the time the invention was made to different width of the bottom portion of the ridge in the first and second region and a resonator length, since it has been held that where the general conditions of a claim are

disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233.

In addition, the selection of different width of the bottom portion of the ridge in the first and second region and a resonator length, it's obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. *In re Woodruff*, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also *In re Huang*, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996) (claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also *In re Boesch*, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and *In re Aller*, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed [width of the bottom portion of the ridge in the first region is in a range of 1.8 μm to 2.5 μm , a difference between the width of the bottom portion of the ridge in the first region and a maximum width of the bottom portion of the ridge in the second region is in a range of 0.5 μm or less, and the resonator length is in a range of 800 μm to 1500 μm] or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen [width of the bottom portion of the ridge in the first region

is in a range of 1.8 μm to 2.5 μm , a difference between the width of the bottom portion of the ridge in the first region and a maximum width of the bottom portion of the ridge in the second region is in a range of 0.5 μm or less, and the resonator length is in a range of 800 μm to 1500 μm] or upon another variable recited in a claim, the Applicant must show that the chosen [width of the bottom portion of the ridge in the first region is in a range of 1.8 μm to 2.5 μm , a difference between the width of the bottom portion of the ridge in the first region and a maximum width of the bottom portion of the ridge in the second region is in a range of 0.5 μm or less, and the resonator length is in a range of 800 μm to 1500 μm] are critical. In re Woodruff, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Shimoyama discloses the claimed invention except for length of the first region is 10% to 50% with respect to a resonator length. It would have been obvious to one having ordinary skill in the art at the time the invention was made to a length of the first region with respect to the resonator length, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233.

In addition, the selection of a region with respect to a resonator length, it's obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. *In re Woodruff*, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also *In re Huang*, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996)

(claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also *In re Boesch*, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and *In re Aller*, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed [a length of the first region being 10% to 50% with respect to a resonator length] or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen [a length of the first region being 10% to 50% with respect to a resonator length] or upon another variable recited in a claim, the Applicant must show that the chosen [a length of the first region being 10% to 50% with respect to a resonator length] are critical. *In re Woodruff*, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Claims 24 – 26 and 36 – 38 are rejected under 35 U.S.C. 103 (a) as being unpatentable over Shimoyama Kenji (JP 2000-312052) in views of Doi et al. (5,679,947).

Regarding claims 24 – 25 and 36 – 37, Shimoyama Kenji discloses the claimed invention except for reflection mirror. However, it is well known in the art to apply

the reflection mirror as disclosed by Doi in Figure 1. Therefore, it would have been obvious to a person having ordinary skill in the art at the time the invention was to apply the well known reflection mirror as suggested by Doi to the semiconductor laser of Shimoyama Kenji, because could be using to reflecting a laser beam.

Regarding claims 26 and 38, Shimoyama discloses the semiconductor laser device is formed on the substrate (see Fig. 1A Character 101).

Response to Arguments

Applicant's arguments filed April 25, 2008 have been fully considered but they are not persuasive. Applicant argues the prior art lacks: "Shimoyama et al. fail to disclose a second region where the width of a bottom portion of a ridge is varied continuously in an optical path direction and the second region being placed between a first region and an end face in an optical path. Nor do Shimoyama et al. disclose a length of the first region being 10% to 50% with respect to a resonator length".

The examiner disagrees with the applicant's argument since the prior art does teach a second region (See Fig. 3a, Characters W_t) where the width of the bottom portion of the ridge is varied continuously, and the second region (see Fig. 3a, Characters W_t) is placed between the first region (see Fig. 3a, Character W_c) and an end face (see Fig. 3a, Character W_R) in an optical path, and end face in an optical path and a length of the first region being 10% to 50% with respect to a resonator length. It

would have been obvious to one having ordinary skill in the art at the time the invention was made to a length of the first region with respect to the resonator length, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only routine skill in the art. *In re Aller*, 105 USPQ 233.

In addition, the selection of a first region with respect to a resonator length, it's obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior art range. *In re Woodruff*, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also *In re Huang*, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996) (claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also *In re Boesch*, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and *In re Aller*, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed [a length of the first region being 10% to 50% with respect to a resonator length] or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen [a length of the first region being 10% to 50% with respect to a resonator length] or upon another variable recited in a claim, the Applicant must

show that the chosen [a length of the first region being 10% to 50% with respect to a resonator length] are critical. In re Woodruff, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Applicant's arguments fail to comply with 37 CFR 1.111(b) because they amount to a general allegation that the claims define a patentable invention without specifically pointing out how the language of the claims patentably distinguishes them from the references.

Applicant's arguments do not comply with 37 CFR 1.111(c) because they do not clearly point out the patentable novelty which he or she thinks the claims present in view of the state of the art disclosed by the references cited or the objections made. Further, they do not show how the amendments avoid such references or objections.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the

shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Delma R. Fordé whose telephone number is (571) 272-1940. The examiner can normally be reached on M - T.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Min Sun Harvey can be reached on (571) -272-1835. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/Delma R. Fordé/
Examiner, Art Unit 2828

Art Unit: 2828

/Minsun Harvey/

Supervisory Patent Examiner, Art Unit 2828